Electronic Supplementary Material (ESI) for RSC Advances.

A novel functional group difference-based selective etching strategy for the synthesis of hollow organic silica nanospheres

Fanlong Zeng,[a] Lianxi Chen,*[a] Jie Li,[ab] Xinshan Ye,[c] Huogen Yu,[a] Zhenhui Liu[a]

[a] School of Chemistry, Chemical Engineering and Life Sciences, Wuhan University of Technology, Wuhan, 430070, P. R. China. E-mail: clx@whut.edu.cn.
[b] School of Materials Science and Engineering, Wuhan University of Technology, Wuhan, 430070, P. R. China.
[c] Stake Key Laboratory of Natural and Biomimetic Drugs, Peking University, Bejing, 100191, P. R. China.

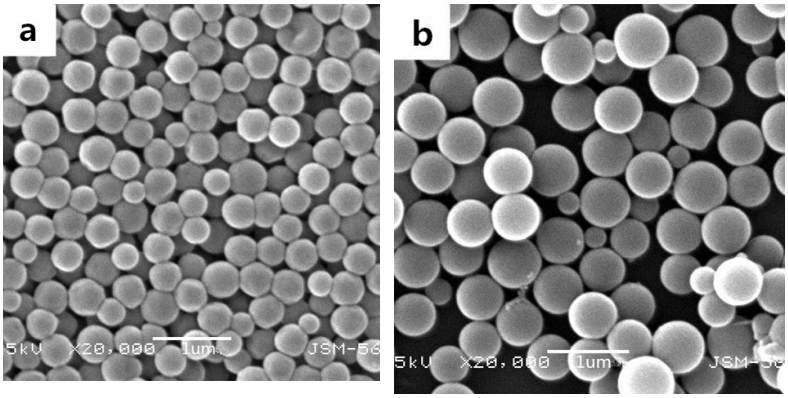

Fig. S1. Typical SEM images of the initial (a) VTES@TCPTES by hydrothermal treatment and (b) TEOS@TCPTES by hydrothermal treatment, respectively.

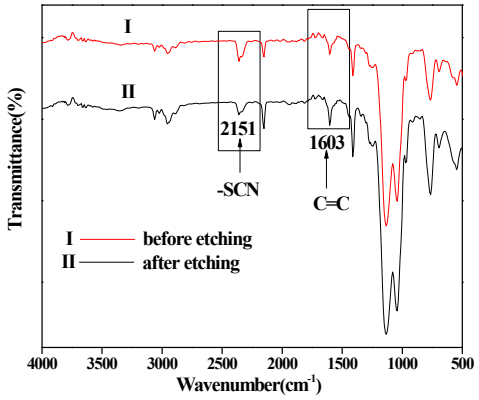

Fig. S2. Typical SEM images of the initial VTES@TCPTES by hydrothermal treatment (I) and VTES@TCPTES by hydrothermal treatment in Na_2CO_3 solution at 50 ℃ for 10 h, respectively.

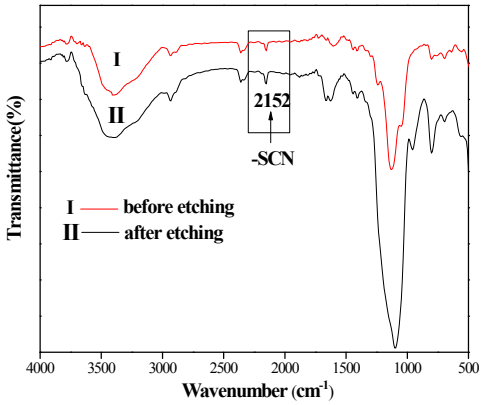

Fig. S3. Typical SEM images of (I) the initial TEOS@TCPTES by hydrothermal treatment and (II) TEOS@TCPTES by hydrothermal treatment in Na_2CO_3 solution at 50 ℃ for 10 h, respectively.